

IN THE CLAIMS:

Please substitute the following claims for the same-numbered claims in the application:

1. (Currently Amended) A method of producing ~~[[a]]~~ an optimum critical dimension value, said method comprising:

determining a stepper focus parameter;

combining said stepper focus parameter with a critical dimension measurement to remove structural bias from critical dimension information; and

generating said optimum critical dimension value from said combining.

2. (Currently Amended) The method of claim 1, wherein said ~~step of determining a stepper focus~~ comprises:

navigating to a stepper focus monitor target;

performing a scanning electron microscope focusing; and

performing a final alignment of said target.

3. (Currently Amended) The method of claim 2, wherein said ~~step of determining a stepper focus~~ further comprises:

acquiring a waveform data;

analyzing said waveform data; and

determining said stepper focus parameter based on said analyzing.

4. (Currently Amended) The method of claim 2, wherein said ~~step of determining a stepper focus~~ further comprises:

acquiring an image data;

analyzing said image data; and

determining said stepper focus parameter based on said analyzing.

5. (Currently Amended) The method of claim 1, wherein said ~~step of generating a critical dimension value~~ comprises:

navigating to a critical dimension structure;

performing a scanning electron microscope focusing; and

performing a final alignment of said critical dimension structure.

6. (Currently Amended) The method of claim 5, wherein said ~~step of generating a critical dimension value~~ further comprises:

acquiring a waveform data;

analyzing said waveform data; and

determining said optimum critical dimension value based on said analyzing.

7. (Currently Amended) The method of claim 5, wherein said ~~step of generating a critical dimension value~~ further comprises:

acquiring an image data;

analyzing said image data; and

determining said optimum critical dimension value based on said analyzing.

8. (Currently Amended) A method of producing ~~[[a]]~~ an optimum critical dimension value,

said method comprising:

generating a scanning electron microscope focus;

generating a waveform data based on output from said scanning electron microscope focus;

analyzing said waveform data to determine a critical dimension measurement;

analyzing said waveform data to determine a stepper focus parameter;

combining said stepper focus parameter with said critical dimension measurement to

remove structural bias from critical dimension information; and

generating said optimum critical dimension value from said combining.

9. (Currently Amended) The method of claim 8, wherein said ~~step of~~ generating a waveform data further comprises:

navigating to a critical dimension structure;

performing a scanning electron microscope focusing;

performing a final alignment of said critical dimension structure; and

acquiring said waveform data based on said scanning electron microscope focusing and said final alignment.

10. (Currently Amended) A method of producing ~~[[a]]~~ an optimum critical dimension value, said method comprising:

generating a scanning electron microscope focus;

generating an image data based on output from said scanning electron microscope focus;

analyzing said image data to determine a critical dimension measurement;

analyzing said image data to determine a stepper focus parameter;
combining said stepper focus parameter with said critical dimension measurement to remove structural bias from critical dimension information; and
generating said optimum critical dimension value from said combining.

11. (Currently Amended) The method of claim 10, wherein said ~~step of~~ generating an image data further comprises:

navigating to a critical dimension structure;
performing a scanning electron microscope focusing;
performing a final alignment of said critical dimension structure; and
acquiring said image data based on said scanning electron microscope focusing and said final alignment.

12. (Currently Amended) A method of producing ~~[[a]]~~ an optimum critical dimension value, said method comprising:

determining a stepper focus parameter;
measuring a critical dimension measurement;
combining said stepper focus parameter with said critical dimension measurement to remove structural bias from critical dimension information; and
generating said optimum critical dimension value based on said combining.

13. (Currently Amended) The method of claim 12, wherein said ~~step of~~ determining a stepper focus comprises:

navigating to a stepper focus monitor target;
performing a scanning electron microscope focusing; and
performing a final alignment of said target.

14. (Currently Amended) The method of claim 13, wherein said ~~step of determining a stepper focus~~ further comprises:

acquiring a waveform data;
analyzing said waveform data; and
determining said stepper focus parameter based on said analyzing.

15. (Currently Amended) The method of claim 13, wherein said ~~step of determining a stepper focus~~ further comprises:

acquiring an image data;
analyzing said image data; and
determining said stepper focus parameter based on said analyzing.

16. (Currently Amended) The method of claim 12, wherein said ~~step of generating a critical dimension value~~ comprises:

navigating to a critical dimension structure;
performing a scanning electron microscope focusing; and
performing a final alignment of said structure.

17. (Currently Amended) The method of claim 16, wherein said ~~step of generating a critical~~

~~dimension value~~ further comprises:

- acquiring a waveform data;
- analyzing said waveform data; and
- determining said optimum critical dimension value based on said analyzing.

18. (Currently Amended) The method of claim 16, wherein said ~~step of generating a critical dimension value~~ further comprises:

- acquiring an image data;
- analyzing said image data; and
- determining said optimum critical dimension value based on said analyzing.

19. (Currently Amended) A method of producing ~~[[a]]~~ an optimum critical dimension value, said method comprising:

- determining a stepper focus parameter;
- measuring a critical dimension measurement;
- combining said stepper focus parameter with said critical dimension measurement to remove structural bias from critical dimension information; and
- generating said optimum critical dimension value based on said combining;
- wherein said ~~step of determining a stepper focus~~ further comprises:
 - navigating to a stepper focus monitor target;
 - performing a scanning electron microscope focusing at said target;
 - performing a final alignment of said target based on said scanning electron microscope focusing at said target;

acquiring a first data set from said scanning electron microscope focusing;
analyzing said first data set; and
determining said stepper focus parameter based on said analyzing;
wherein said ~~step of generating a critical dimension~~ further comprises:
navigating to a critical dimension structure;
performing a scanning electron microscope focusing at said critical dimension structure;
performing a final alignment of said critical dimension structure;
acquiring a second data set from said scanning electron microscope focusing at said critical dimension structure;
analyzing said second data set; and
determining ~~[[a]]~~ said optimum critical dimension value based on said analyzing.

20. (Currently Amended) A program storage device readable by ~~machine~~ a computer, tangibly embodying a program of instructions executable by the ~~machine~~ computer to perform a method of producing ~~[[a]]~~ an optimum critical dimension value, said method comprising:

determining a stepper focus parameter;

combining said stepper focus parameter with a critical dimension measurement to remove structural bias from critical dimension information; and

generating ~~[[a]]~~ said optimum critical dimension value from said combining.

21. (Currently Amended) The program storage device of claim 20, wherein in said method said ~~step of determining a stepper focus~~ comprises:

navigating to a stepper focus monitor target;
performing a scanning electron microscope focusing; and
performing a final alignment of said target.

22. (Currently Amended) The program storage device of claim 21, wherein in said method
said step of determining a stepper focus further comprises:

acquiring a waveform data;
analyzing said waveform data; and
determining said stepper focus parameter based on said analyzing.

23. (Currently Amended) The program storage device of claim 21, wherein in said method
said step of determining a stepper focus further comprises:

acquiring an image data;
analyzing said image data; and
determining [[a]] said stepper focus parameter based on said analyzing.

24. (Currently Amended) The program storage device of claim 20, wherein in said method
said step of generating a critical dimension value comprises:

navigating to a critical dimension structure;
performing a scanning electron microscope focusing; and
performing a final alignment of said critical dimension structure.

25. (Currently Amended) The program storage device of claim 24, wherein in said method

said ~~step of generating a critical dimension value~~ further comprises:

acquiring a waveform data;

analyzing said waveform data; and

determining said optimum critical dimension value based on said analyzing.

26. (Currently Amended) The program storage device of claim 24, wherein in said method

said ~~step of generating a critical dimension value~~ further comprises:

acquiring an image data;

analyzing said image data; and

determining said optimum critical dimension value based on said analyzing.